

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2656	((auxiliary secondary inspection) adj3 (pattern layout area film membrane) same ((\$mask reticle)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/05 07:29
L2	435	L1 and 430/5.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/05 07:29
L3	979	1 and (electron x\$1ray x adj ray stencil membrane)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/05 07:32
L4	265	2 and (electron x\$1ray x adj ray stencil membrane)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/05 07:33
L6	21	(US-20060008707-\$ or US-20030031936-\$ or US-20020000524-\$ or US-20010021546-\$).did. or (US-5958627-\$ or US-5260151-\$ or US-7109500-\$ or US-7060996-\$ or US-6787785-\$ or US-5866281-\$ or US-5959304-\$ or US-6277532-\$ or US-6531249-\$ or US-5876881-\$ or US-6603120-\$ or US-6222195-\$ or US-6936931-\$ or US-6638665-\$).did. or (WO-2004003664-\$ or EP-1536283-\$).did. or (JP-2007110154-\$).did. or (US-20020000524-A-\$).did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2008/06/05 11:19
L7	7	6 and (beam near2 scatter \$3 beam\$1scatter\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/05 11:20
L8	2	6 and flexure	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/05 13:22

S1	79	("2002"\$4"524"\$5 and nikon.as.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 07:10
S2	1	("5958627").PN.	USPAT; USOCR	OR	OFF	2008/02/12 07:14
S3	1	("5260151").PN.	USPAT; USOCR	OR	OFF	2008/02/12 07:15
S4	113	(membrane stencil) near2 (\$6mask reticle reticule) same (inspect\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 09:39
S5	43	((thin near2 film) membrane) same S4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 09:40
S6	1	((((membrane stencil) near2 (\$6mask reticle reticule)) same (inspect \$4 near3 (film layer))) and ((thin near2 film) membrane)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 10:08
S7	9	((((membrane stencil) near2 (\$6mask reticle reticule)) and (inspect\$4 near3 (film layer))) same ((thin near2 film) membrane)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 10:09
S8	1	((((membrane stencil) near2 (\$6mask reticle reticule)) same (inspect \$4 near3 (film layer))) same ((thin near2 film) membrane)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 10:19
S9	713	(inspect\$4 adj3 (film layer)) same ((thin near2 film) membrane)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 10:20
S10	931497	(thick support\$3) near3 (substrate frame film)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 10:21
S11	26	S9 same S10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 10:22
S12	25	S11 not S5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 10:22

S13	19	((YOKO) near2 (WATANABE)).INV.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/02/12 10:32
S14	28	((SHINJI) near2 (OMORI)).INV.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/02/12 10:37
S15	1	((KAZUYA) near2 (IWASE)).INV.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/02/12 10:52
S16	1	((KEIKO) near2 (AMAI)).INV.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/02/12 10:52
S17	33	((MASAKI) near2 (YOSHIZAWA)).INV.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/02/12 10:53
S18	5512	(membrane stencil) near2 (\$mask reticle reticle)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:15
S19	534	(inspect\$4 adj2 (mask pattern film membrane)) same (thin near2 (mask pattern film membrane))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:17
S20	8	S18 same S19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:17
S21	0	S20 not S5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:17
S22	1	(S18 and S19) not S5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:17
S23	558	(inspect\$4 adj2 (mask pattern film membrane area)) same (thin near2 (mask pattern film membrane))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:19
S24	1	(S18 and S23) not S5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:20
S25	0	(S18 and S23) not (S5 S22)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:20
S26	634999	(inspect\$4 near S2(mask pattern film membrane area)) same (thin near2 (mask pattern film membrane))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:20

S27	923	((inspect\$4 near2 (mask pattern film membrane area)) same (thin near2 (mask pattern film membrane)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:21
S28	13	S18 same S27	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:21
S29	151	S27 and S10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:27
S30	33	S27 same S10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:27
S31	29	S30 not S5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:27
S32	29	S30 not (S5 S28)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 11:27
S33	2118	inspect\$4 adj3 (pattern layout area film membrane) same (\$6mask reticle)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 13:01
S34	1274	inspection adj3 (pattern layout area film membrane) same (\$6mask reticle)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 13:05
S35	18	inspection adj3 (pattern layout area film membrane) same ((stencil membrane) near2 (\$6mask reticle))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 13:07
S36	43	((auxiliary secondary inspection) adj3 (pattern layout area film membrane) same ((stencil membrane) near2 (\$6mask reticle)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 13:10
S37	25	S36 not S35	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 13:10

S38	2	((thin adj2 film) near2 exposure) same ((thick adj2 film) with support \$3) same ((thin adj2film) near2 inspect\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:05
S39	2	((thin adj2 film) near2 exposure) and ((thick adj2 film) with support \$3) and((thin adj2film) near2 inspect\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:06
S40	2	((thin adj2 film) near2 exposure) and ((thick adj2 film) with support \$3) and ((thin adj2film) near2 inspect\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:06
S41	695	((thin adj2 film) near2 inspect\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:07
S42	364	((thin adj2 film) near2 inspection)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:07
S43	113	((membrane stencil) near2 (\$6mask reticle reticule) same (inspect\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:08
S44	1	((thin adj2 film) near2 inspection) same S43	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:08
S45	1	((thin adj2 film) near2 inspection) same ((membrane stencil) near2 (\$6mask reticle reticule))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:08
S46	4	((thin adj2 film) near2 inspection) and ((membrane stencil) near2 (\$6mask reticle reticule))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:09
S47	3	S46 not S44	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:10
S48	3	S46 not S38	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:10

S49	0	09/828300.ap.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:12
S50	0	"09"\$1"828300".ap.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:12
S51	0	"09828300".ap.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:12
S52	2	09/828300	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/02/12 14:12
S53	1	("5866281").PN.	USPAT; USOCR	OR	OFF	2008/06/03 13:09
S54	5	"2002000524"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/03 13:14
S55	2	"2002000524"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/03 13:16
S56	5	"2001021546"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/03 13:20
S57	2	"20010021546"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/03 13:20
S58	3	((("6277532") or ("5959304") or ("6531249")).PN.	USPAT; USOCR	OR	OFF	2008/06/03 13:43
S59	4074	stencil near2 (\$6mask reticle)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/03 13:56
S60	80	S59 same inspection	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/03 13:57
S61	1	(stencil near2 (\$6mask reticle)) same (inspect\$4 near2 (film layer))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/04 10:06

S62	20	(stencil near2 (\$mask reticle)) and (inspect\$4 near2 (film layer))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/04 10:07
S63	85837	(\$mask reticle) same (membrane stencil beam electronbeam)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/04 14:13
S64	2210	S63 same inspection	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/04 14:25
S65	1003	S64 and \$6resist	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/04 14:27
S66	1522	(((\$mask reticle) with (membrane stencil beam electronbeam)) same inspection	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/04 14:28
S67	77	\$66 and (beam adj scatter \$3 beam\$1scatter\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/04 14:44
S68	580	(((\$mask reticle) with (membrane stencil beam electronbeam)) same (inspection with (area membrane pattern))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/04 15:01
S69	160	(((\$mask reticle) near2 (membrane stencil beam electronbeam)) same (inspection with (area membrane pattern))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/04 15:06
S70	160	(((\$mask reticle) near2 (membrane stencil beam electronbeam)) same (inspection with (area membrane pattern))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/04 15:06
S71	43	((auxiliary secondary inspection) adj3 (pattern layout area film membrane) same ((stencil membrane) near2 (\$mask reticle)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/04 15:44
S72	2654	((auxiliary secondary inspection) adj3 (pattern layout area film membrane) same (((\$mask reticle)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/04 15:58

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